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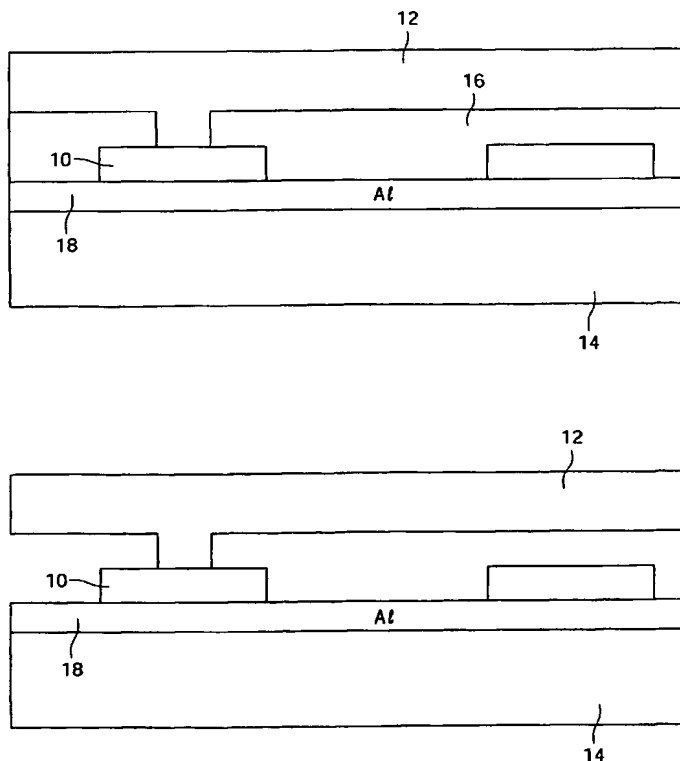
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(54) Title: A METHOD OF MANUFACTURING AN ELECTRONIC DEVICE AND ELECTRONIC DEVICE



(57) Abstract: 16 ABSTRACT:
A method of manufacturing a micro-electromechanical systems (MEMS) device, comprising providing a base layer (10) and a mechanical layer (12) on a substrate (14), providing a sacrificial layer (16) between the base layer (10) and the mechanical layer (12), providing an etch stop layer (18) between the sacrificial layer (16) and the substrate (14), and removing the sacrificial layer (16) by means of dry chemical etching, wherein the dry chemical etching is performed using a fluorine-containing plasma, and the etch stop layer (18) comprises a substantially non-conducting, fluorine chemistry inert material, such as HfO_2 , ZrO_2 , Al_2O_3 or TiO_2 .

**Declaration under Rule 4.17:**

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